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(54) Title: REACTOR AND METHOD FOR PRODUCTION OF SILICON

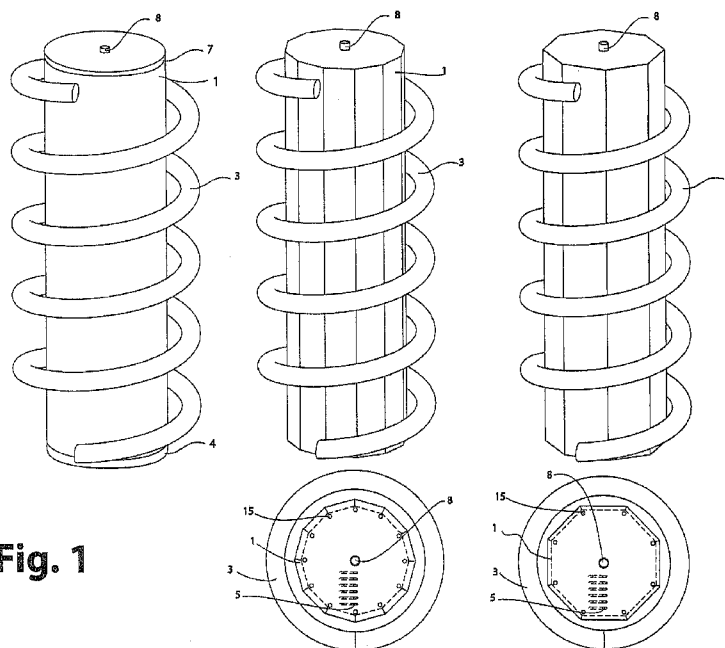


Fig. 1

(57) Abstract: Reactor for production of silicon, comprising a reactor volume, distinctive in that the reactor comprises or is operatively arranged to at least one means for setting a silicon-containing reaction gas for chemical vapor deposition (CVD) into rotation inside the reactor volume. Method for production of silicon.



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